# Simultaneous Control of Subthreshold and Gate Leakage Current in Nanometer-Scale CMOS Circuits

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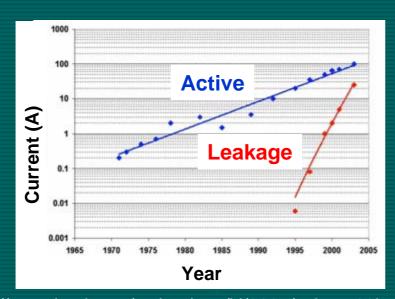
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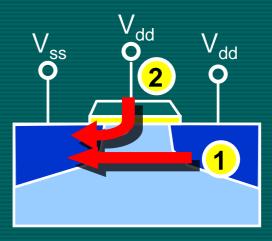
### **Outline**

- Introduction: leakage current, power gating
- Supply switching with ground collapse (SSGC)
- Implementation of SSGC
- Experimental results
- Summary

# Leakage Current

- Leakage current in nanometer regime
  - Exponential growth of leakage
    - Subthreshold leakage due to reduced V<sub>th</sub> 1
    - Gate leakage due to reduced T<sub>ox</sub> 2

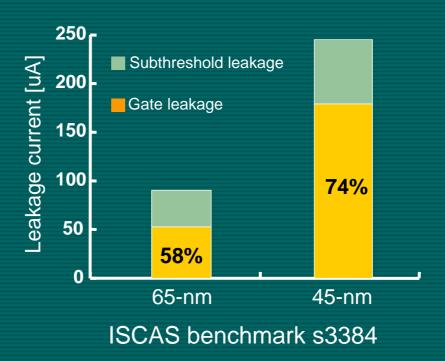




http://www.intel.com/technology/itj/2005/volume09issue04/art01\_advpackagetech/p04\_techtrends.htm

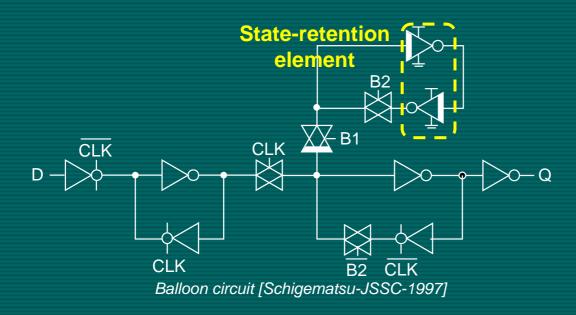
# Leakage Current

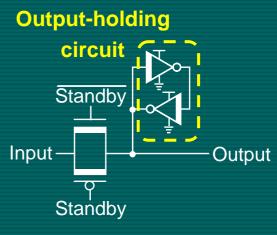
- Gate leakage current
  - Grow faster than subthreshold leakage
  - May dictate the total leakage in future technology



## **Power Gating**

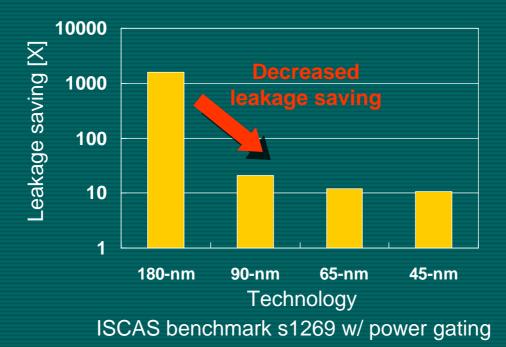
- Power gating
  - Widely used to suppress subthreshold leakage
  - Active mode: footer turned-on
  - Standby mode: footer cuts off power rail





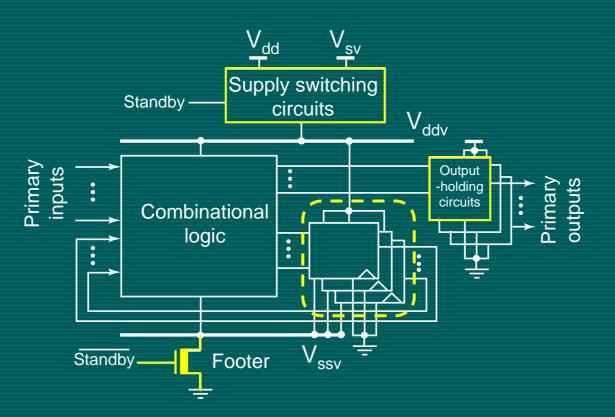
## **Power Gating**

- Power gating in nanometer regime
  - State-retention and output-holding circuit leak gate leakage
  - Leakage saving from power gating greatly reduced



## Supply Switching with Ground Collapse

SSGC: supply control + power gating



#### **Active**

Supply switching

circuits: V<sub>dd</sub>

Footer: on

#### **Standby**

Supply switching

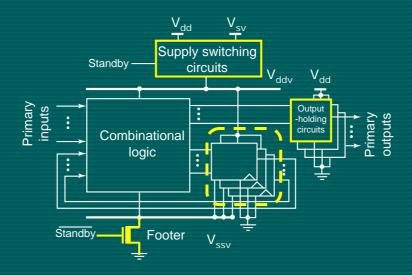
circuits: V<sub>sv</sub> (<V<sub>dd</sub>)

Footer: off

## Supply Switching with Ground Collapse

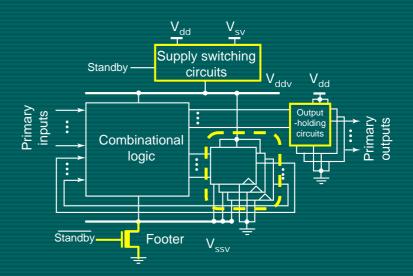
#### SSGC circuit

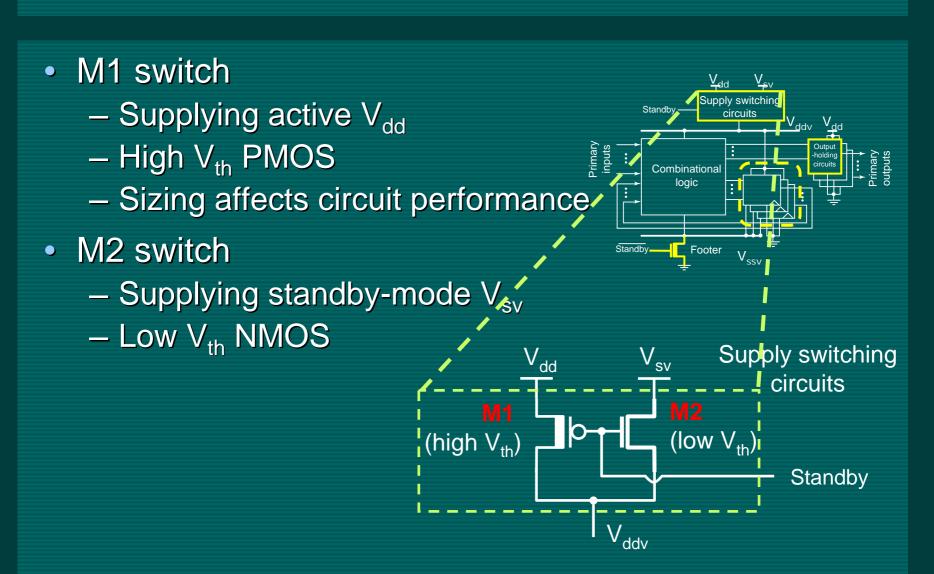
- Reduce leakage of combinational logic through power gating (ground collapse)
- Reduce leakage of FF through lowered voltage (supply switching) and power gating
- No need to use state-retention FF



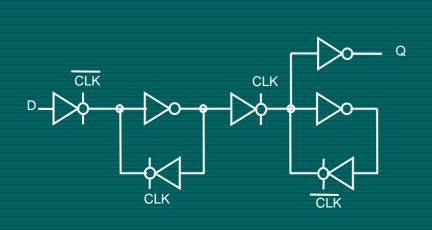
# Supply Switching with Ground Collapse

- Implementation of SSGC
  - Design of supply switching circuits
  - Physical design
    - Power networks
    - SSGC flip-flop
    - Footer
    - Output-holding circuit

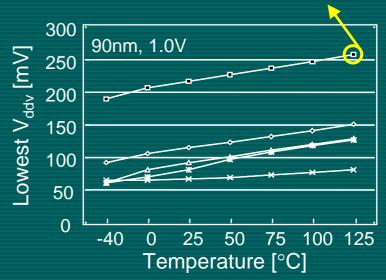




- V<sub>ddv</sub> in standby
  - Bounded by the potential to retain states in FFs + noise margin
  - Factors: temperature, process variation, states (0 or 1), FF types



#### 260mV for state retention

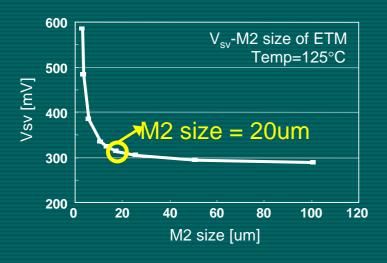


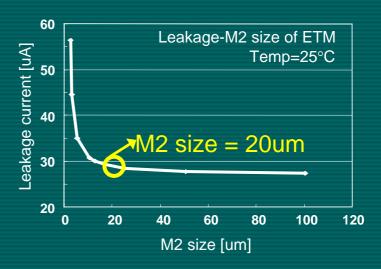
- Design of M2 switch
  - Selection of M2 size and V<sub>sv</sub> for
    - Efficient leakage saving
    - Lowest V<sub>ddv</sub> (e.g. 260mV)
  - Voltage drop across M2 dictates V<sub>sv</sub>

# M2 size and $V_{sv}$ $V_{sv} = V_{ddv} + I_{leakage} \times R_{M2}$ $R_{M2} = \frac{R_{min}}{M2 \ size}$ $R_{M2} = \frac{R_{min}}{M2 \ size}$

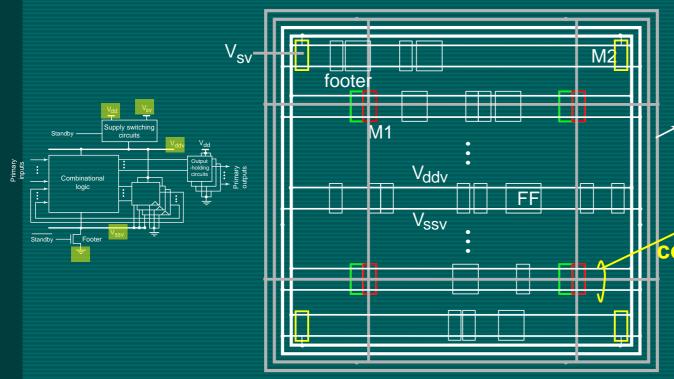
- Design of M2 switch
  - M2 size vs. V<sub>sv</sub>
    - Trade-off between area overhead and leakage power

$$V_{sv} = V_{ddv} + I_{leakage} \times \frac{R_{min}}{M2 \ size}$$





- Power networks for SSGC
  - Conventional  $V_{dd}$  and  $V_{ss}$  rails as  $V_{ddv}$  and  $V_{ssv}$  rails



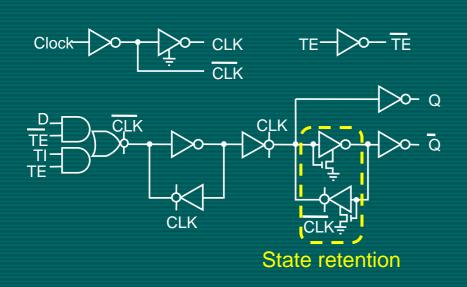
V<sub>dd</sub>: vertical rails

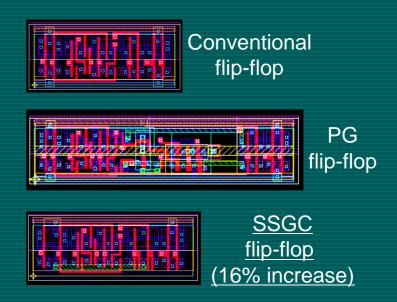
V<sub>ss</sub>: horizontal rails

 $V_{SS}$ 

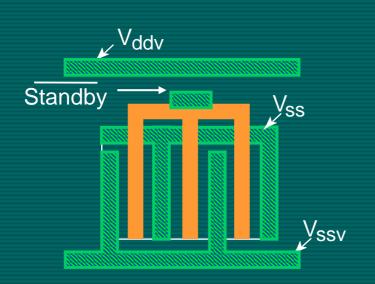
V<sub>ddv</sub> and V<sub>ssv</sub> rails for combinational logic cells

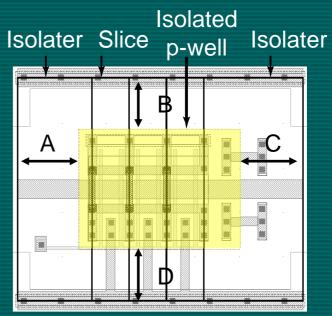
- SSGC flip-flop
  - State maintained in slave latch with low V<sub>sv</sub>
    - No need of state-retention element
    - Low gate and subthreshold leakage current
      - Other parts are power gated for further reduction



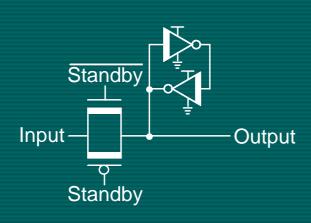


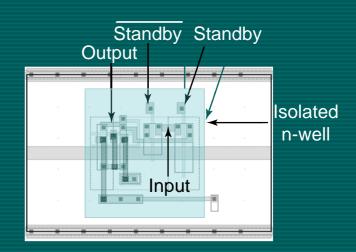
- Footer layout
  - Isolated body (body bias to V<sub>ss</sub>) preferred for leakage current → area overhead due to well isolation
  - Building block-based approach: flexible placement, control of area overhead



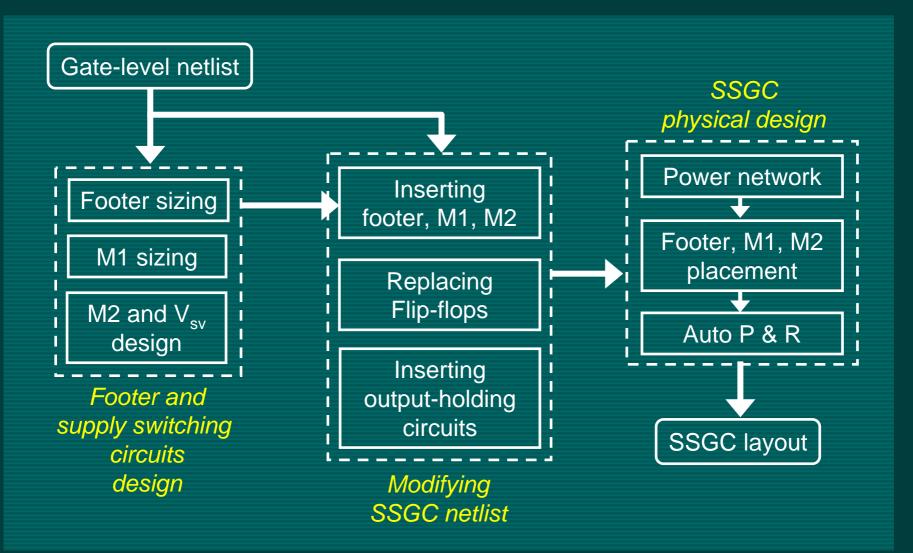


- Output-holding circuit
  - Output-holding circuits are needed due to V<sub>sv</sub>(<V<sub>dd</sub>) in standby
  - Utilize high V<sub>th</sub> to reduce subthreshold leakage



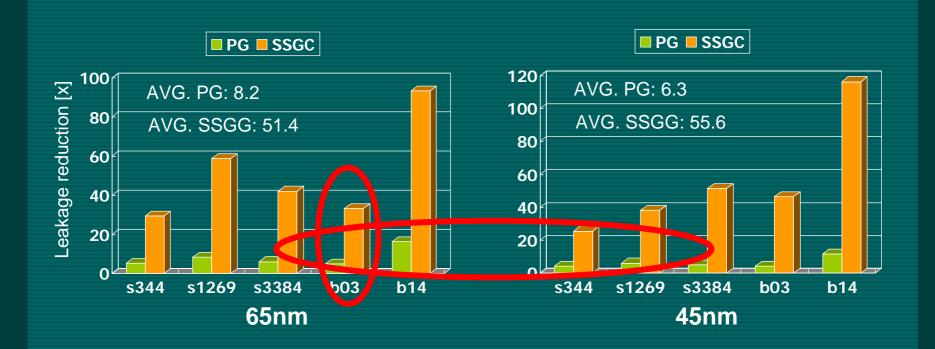


# **SSGC Design Flow**



## **Experimental Results**

- Test circuits
  - ISCAS and ITC benchmark circuits
  - 65- and 45-nm predictive models

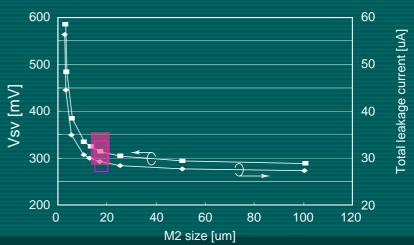


# Case Study: ETM

- Embedded Trace Macrocell (ETM)
  - Debugging and tracing core for ARM
  - 90nm, 1.0V commercial process

I / Os	SEs	Gates	Leakage
320 / 124	5,501	90,068	410uA

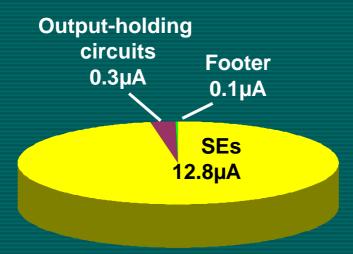
- Footer, M1, and M2 sizing
  - M1 and footer sizing for 10% delay increase
  - M2 sizing to optimize leakage at room temperature

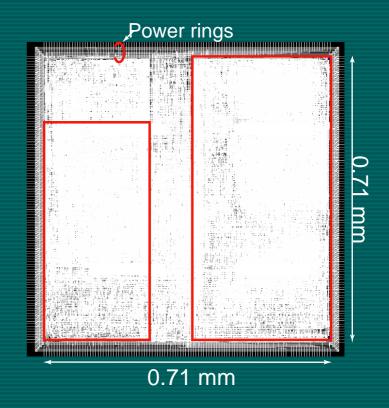


# **Case Study: ETM**

- SSGC implementation result
  - Total leakage saving: 32x at 25°C
  - Area increase: 3%
  - Wirelength increase: 6%

### Leakage current breakdown





## Summary

- Power gating
  - Widely used to suppress subthreshold leakage
  - NOT efficient in nanometer technology due to gate leakage of storage elements and output-holding circuits
- Supply switching with ground collapse
  - Overcomes the limitation of power gating
  - Demonstrates cell-based semicustom design flow based on SSGC